

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Gautam V. Thakar, et al.

Art Unit: 1765

Division of Serial No.: 09/939,259

Examiner: Binh X. Tran

Filed: Herewith

Docket: TI-32822.1

For: Polysilicon Processing Using an Anti-Reflective Dual Layer Hardmask for 193 nm Lithography

"EXPRESS MAILING" Mailing Label No. EV334469269US. I hereby certify that this paper is being deposited with the U.S. Postal Service Express Mail Post Office to Addressee Service under 37 CFR 1.10 on the date shown below and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

Karen Vertz

Karen Vertz

8-21-03

Date

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**PRELIMINARY AMENDMENT**

Dear Sir:

Prior to the examination of the above-identified application, please amend as follows:

**IN THE CLAIMS:**

Please cancel Claims 1-7, 9 and 11-17.

Should the Examiner have any further comments or suggestions, it is respectfully requested that the Examiner contact the undersigned in order to expeditiously resolve any outstanding issues.

Respectfully submitted,

  
Gary C. Honeycutt  
Reg. No. 20,250  
Attorney for Applicants

Texas Instruments Incorporated  
P.O. Box 655474 M/S 3999  
Dallas, Texas 75265  
(972) 470-0130